6.012 Electronic Devices and Circuits
Formula Sheet for Final Exam, Fall 2003

Parameter Values:

$q \; = \; 1.6 x 10^{\;\;19} \; Coul$

${}_{o} = \; 8.854 x 10^{\;\;14} \; F/cm, \quad {}_{r,Si} = \; 11.7, \quad {}_{r,SiO_2} \; = \; 3.9$

${}_{Si} \quad 10^{\;\;12} \; F/cm, \quad {}_{SiO_2} \quad 3.5 \, x 10^{\;\;13} \; F/cm$

$n_i[Si@R.T] \quad 10^{10} \; cm^{\;\;3}$

$kT/q \quad 0.025\,V; \quad (kT/q)\ln 10 \quad 0.06\,V$

$1 \quad m = 1x10^{\;\;4} \; cm$

Periodic Table:

III	IV	V
B	C	N
Al	Si	P
Ga	Ge	As
In	Sn	Sb

Drift/Diffusion:

Drift velocity: $\bar{s}_x = \pm \;\; {}_m E_x$

Conductivity: $\quad = q(\;\; {}_e n + \;\; {}_h p)$

Diffusion flux: $F_m = \quad D_m \dfrac{\partial C_m}{\partial x}$

Einstein relation: $\dfrac{D_m}{{}_m} = \dfrac{kT}{q}$

Electrostatics:

$$\frac{dE(x)}{dx} = \quad (x) \qquad E(x) = \frac{1}{\;} \qquad (x)dx$$

$$\frac{d \;\; (x)}{dx} = E(x) \qquad (x) = \qquad E(x)dx$$

$$\frac{d^2 \;\; (x)}{dx^2} = \quad (x) \qquad (x) = \quad \frac{1}{\;} \qquad (x)dxdx$$

The Five Basic Equations:

Electron concentration: $\dfrac{\partial n(x,t)}{\partial t} \quad \dfrac{1}{q}\dfrac{\partial J_e(x,t)}{\partial x} = g_L(x,t) \quad \left[n(x,t)\cdot p(x,t) \quad n_i^2\right]r(T)$

Hole concentraton: $\dfrac{\partial p(x,t)}{\partial t} + \dfrac{1}{q}\dfrac{\partial J_h(x,t)}{\partial x} = g_L(x,t) \quad \left[n(x,t)\cdot p(x,t) \quad n_i^2\right]r(T)$

Electron current density: $J_e(x,t) = q \quad {}_e n(x,t)E(x,t) + qD_e \dfrac{\partial n(x,t)}{\partial x}$

Hole current density: $J_h(x,t) = q \quad {}_h p(x,t)E(x,t) \quad qD_h \dfrac{\partial p(x,t)}{\partial x}$

Poisson's equation: $\dfrac{\partial E(x,t)}{\partial x} = \; \dfrac{q}{\;}\left[p(x,t) \quad n(x,t) + N_d^+(x) \quad N_a(x)\right]$

Uniform doping, full ionization, TE

n - type, $N_d >> N_a$

$$n_o \quad N_d \quad N_a \equiv N_D, \quad p_o = n_i^2/n_o, \qquad {}_n = \frac{kT}{q}\ln\frac{N_D}{n_i}$$

p - type, $N_a >> N_d$

$$p_o \quad N_a \quad N_d \equiv N_A, \quad n_o = n_i^2/p_o, \qquad {}_p = \quad \frac{kT}{q}\ln\frac{N_A}{n_i}$$

Uniform optical excitation, uniform doping

$$n = n_o + n' \qquad p = p_o + p' \qquad n' = p' \qquad \frac{dn'}{dt} = g_l(t) \quad (p_o + n_o + n')n'r$$

Low level injection, $n',p' << p_o + n_o$: $\quad \dfrac{dn'}{dt} + \dfrac{n'}{{}_{min}} = g_l(t) \quad$ with $\quad {}_{min} \quad (p_o r)^{\;\;1}$

Flow problems (uniformly doped quasineutral regions with quasi-static excitation and low level injection; p-type example):

Minority carrier excess: $\dfrac{d^2 n'(x)}{dx^2} \quad \dfrac{n'(x)}{L_e^2} = \quad \dfrac{1}{D_e} g_L(x)$ $\qquad L_e \equiv \sqrt{D_e \quad _e}$

Minority carrier current density: $J_e(x) \quad qD_e \dfrac{dn'(t)}{dx}$

Majority carrier current density: $J_h(x) \;=\; J_{Tot} \quad J_e(x)$

Electric field: $E_x(x) \quad \dfrac{1}{q \quad _h p_o} J_h(x) \quad \dfrac{D_h}{D_e} J_e(x)$

Majority carrier excess: $p'(x) \quad n'(x) + \dfrac{}{q} \dfrac{dE_x(x)}{dx}$

Non-uniformly doped semiconductor sample in thermal equilibrium

$$\frac{d^2 \quad (x)}{dx^2} = \frac{q}{} \left\{ n_i \left[e^{q \quad (x)/kT} \quad e^{\quad q \quad (x)/kT} \right] \quad \left[N_d(x) \quad N_a(x) \right] \right\}$$

$$n_o(x) = n_i e^{q \quad (x)/kT}, \quad p_o(x) = n_i e^{\quad q \quad (x)/kT}, \quad p_o(x) n_o(x) = n_i^2$$

Depletion approximation for abrupt p-n junction:

$$(x) \;=\; \begin{cases} 0 & \text{for} \quad x < \quad x_p \\ qN_{Ap} & \text{for} \quad x_p < x < 0 \\ qN_{Dn} & \text{for} \quad 0 < x < x_n \\ 0 & \text{for} \quad x_n < x \end{cases}$$

$$N_{Ap} x_p = N_{Dn} x_n$$

$$_b \equiv \quad _n \quad _p = \frac{kT}{q} \ln \frac{N_{Dn} N_{Ap}}{n_i^2}$$

$$w(v_{AB}) = \sqrt{\frac{2 \quad _{Si} \left(\quad _b \quad v_{AB} \right)}{q} \frac{\left(N_{Ap} + N_{Dn} \right)}{N_{Ap} N_{Dn}}} \qquad \left| E_{pk} \right| = \sqrt{\frac{2q \left(\quad _b \quad v_{AB} \right)}{_{Si}} \frac{N_{Ap} N_{Dn}}{\left(N_{Ap} + N_{Dn} \right)}}$$

$$q_{DP}(v_{AB}) = \quad AqN_{Ap} x_p(v_{AB}) = \quad A \sqrt{2q \quad _{Si} \left(\quad _b \quad v_{AB} \right) \frac{N_{Ap} N_{Dn}}{\left(N_{Ap} + N_{Dn} \right)}}$$

Ideal p-n junction diode i-v relation:

$$n(\text{-}x_p) = \frac{n_i^2}{N_{Ap}} e^{qv_{AB}/kT}, \quad n'(\text{-}x_p) = \frac{n_i^2}{N_{Ap}} \left(e^{qv_{AB}/kT} \quad 1 \right); \qquad p(x_n) = \frac{n_i^2}{N_{Dn}} e^{qv_{AB}/kT}, \quad p'(x_n) = \frac{n_i^2}{N_{Dn}} \left(e^{qv_{AB}/kT} \quad 1 \right)$$

$$i_D \;=\; Aqn_i^2 \left(\frac{D_h}{N_{Dn} w_{n,eff}} + \frac{D_e}{N_{Ap} w_{p,eff}} \right) \left[e^{qv_{AB}/kT} - 1 \right] \qquad w_{m,eff} = \begin{cases} w_m \quad x_m & \text{if} \quad L_m \gg w_m \\ L_m \tanh\left[\left(w_m \quad x_m \right) / L_m \right] & \text{if} \quad L_m \sim w_m \\ L_m & \text{if} \quad L_m \ll w_m \end{cases}$$

$$q_{QNR,p\text{-}side} = Aq \int_{-w_p}^{-x_p} n'(x)\,dx, \qquad q_{QNR,n\text{-}side} = Aq \int_{x_n}^{w_n} p'(x)\,dx, \qquad \text{Note: } p'(x) \quad n'(x) \text{ in QNRs}$$

Ebers-Moll Model for Bipolar Junction Transistor (BJT) characterisitics (npn example; no base width modulation):

$$i_E = i_{hE} + i_{eE} = \quad Aqn_i^2 \quad \frac{D_h}{N_{DE} w_{E,eff}} + \frac{D_e}{N_{AB} w_{B,eff}} \quad \left[e^{qV_{BE}/kT} \quad 1\right]$$

$$_E \equiv \frac{i_{hE}}{i_{eE}} = \frac{D_h}{D_e} \cdot \frac{N_{AB}}{N_{DE}} \cdot \frac{w_{B,eff}}{w_{E,eff}}$$

$$i_C \quad i_{eE}(1 \quad _B) = \quad Aqn_i^2 \frac{D_e}{N_{AB} w_{B,eff}} \left[e^{qV_{BE}/kT} \quad 1\right](1 \quad _B) \qquad \text{with} \qquad _B \quad \frac{w_{B,eff}^2}{2D_e \quad _e} = \frac{w_{B,eff}^2}{2L_e^2}$$

$$i_B \quad i_{hE} + \; _B \, i_{eE} = i_{eE}(\; _E + \; _B) = \quad Aqn_i^2 \frac{D_e}{N_{AB} w_{B,eff}} \left[e^{qV_{BE}/kT} \quad 1\right](\; _E + \; _B)$$

$$_F \equiv \frac{i_C}{i_B} = \frac{(1 \quad _B)}{(\; _E + \; _B)}$$

Large Signal BJT Model in Forward Active Region (FAR) (npn; with base width mod):

$$i_B(v_{BE}, v_{CE}) = I_{BS}\left[e^{qv_{BE}/kT} \quad 1\right] \quad \text{with} \quad I_{BS} \equiv \frac{1}{(\; _o + 1)} I_{ES} = \frac{1}{(\; _o + 1)} Aqn_i^2 \quad \frac{D_{eB}}{w_{B,eff} N_{AB}} + \frac{D_{hE}}{w_{E,eff} N_{DE}}$$

$$i_C(v_{BE}, v_{CE}) = \quad _o[1 + \quad v_{CE}]\, i_B(v_{BE}, v_{CE}) = \quad _o I_{BS}\left[e^{qv_{BE}/kT} \quad 1\right][1 + \quad v_{CE}]$$

$$\text{Break-point model}: \quad v_{BE,on} \quad 0.6V, \quad v_{CE,sat} \quad 0.2V$$

MOS Capacitor:

$$\text{Flat-band voltage}: \quad V_{FB} \equiv v_{GB} \ \text{ at which} \quad (0) = \quad _p \quad _{Si}$$

$$V_{FB} = \quad _p \quad _{Si} \quad _m$$

$$\text{Threshold voltage}: \quad V_T \equiv v_{GC} \ \text{ at which} \quad (0) = \quad _p \quad _{Si} + v_{BC}$$

$$V_T(v_{BC}) = V_{FB} \quad 2 \quad _p \quad _{Si} + \frac{1}{C_{ox}^*}\left\{2 \quad _{Si} qN_A\left[\left|2 \quad _p \quad _{Si}\right| \quad v_{BC}\right]\right\}^{1/2} \qquad x_{DT}(v_{BC}) = \sqrt{\frac{2 \quad _{Si}\left[\left|2 \quad _p \quad _{Si}\right| \quad v_{BC}\right]}{qN_A}}$$

$$\text{Inversion layer sheet charge density}: \quad q_N^* = \quad C_{ox}^*[v_{GC} \quad V_T(v_{BC})]$$

$$\text{Accumulation layer sheet charge density}: \quad q_P^* = \quad C_{ox}^*[v_{GB} \quad V_{FB}(v_{BC})]$$

Gradual Channel Approx. for MOSFET characteristics (n-channel; no channel length mod.):

$$\text{Valid for } v_{BS} \quad 0, \text{ and } \ v_{DS} \geq 0:$$

$$i_G(v_{GS}, v_{DS}, v_{BS}) = 0 \quad \text{and} \quad i_B(v_{GS}, v_{DS}, v_{BS}) = 0$$

$$i_D(v_{GS}, v_{DS}, v_{BS}) = \begin{array}{lll} 0 & \text{for} & \frac{1}{\;}[v_{GS} \quad V_T(v_{BS})] < 0 < v_{DS} \\ \frac{1}{2}\frac{W}{L} \quad _e C_{ox}^*[v_{GS} \quad V_T(v_{BS})]^2 & \text{for} & 0 < \frac{1}{\;}[v_{GS} \quad V_T(v_{BS})] < v_{DS} \\ \frac{W}{L} \quad _e C_{ox}^* \quad v_{GS} \quad V_T(v_{BS}) \quad \frac{v_{DS}}{2} \quad v_{DS} & \text{for} & 0 < v_{DS} < \frac{1}{\;}[v_{GS} \quad V_T(v_{BS})] \end{array}$$

$$\text{with} \quad V_T(v_{BS}) \equiv V_{FB} \quad 2 \quad _p \quad _{Si} + \frac{1}{C_{ox}^*}\left\{2 \quad _{Si} qN_A\left[\left|2 \quad _p \quad _{Si}\right| \quad v_{BS}\right]\right\}^{1/2}$$

$$\equiv 1 + \frac{1}{C_{ox}^*} \quad \frac{_{Si} qN_A}{2\left[\left|2 \quad _p \quad _{Si}\right| \quad v_{BS}\right]}^{1/2} \qquad \mathrm{C}_{\mathrm{ox}}^* \equiv \frac{_{ox}}{t_{ox}}$$

Large Signal MOSFET Model in Saturation (FAR) (n-channel; with base width mod.):

$$i_G(v_{GS}, v_{DS}, v_{BS}) = 0 \qquad i_B(v_{GS}, v_{DS}, v_{BS}) \quad 0$$

$$i_D(v_{GS}, v_{DS}, v_{BS}) = \frac{K}{2}\left[v_{GS} \quad V_T(v_{BS})\right]^2 [1 + \quad v_{DS}]$$

$$\text{with} \quad K \equiv \frac{W}{L} \; {}_e C_{ox}^* \quad \text{and} \quad V_T = V_{FB} \quad 2 \;{}_p\;{}_{Si} + \frac{1}{C_{ox}^*}\left\{2 \;{}_{Si} q N_A \left[\left|2 \;{}_p\;{}_{Si}\right| \quad v_{BS}\right]\right\}^{1/2}$$

Small signal linear equivalent circuits:

p-n Diode

$$g_d = \frac{q}{kT} I_{BS}\, e^{qV_{AB}/kT} \qquad \frac{qI_D}{kT}$$

$$C_d = C_{dp} + C_{df}, \text{ where } \quad C_{dp}(V_{AB}) = A\sqrt{\frac{q \;{}_{Si} N_{Ap}}{2(\;{}_b \quad V_{AB})}} \quad \text{and}$$

$$C_{df}(V_{AB}) = \frac{qI_D}{kT}\frac{\left[w_p \quad x_p\right]^2}{2D_e} = g_d \;{}_d \quad \text{with} \quad {}_d \equiv \frac{\left[w_p \quad x_p\right]^2}{2D_e}$$

BJT (in FAR)

$$g_m \quad \frac{q|I_C|}{kT} \qquad g \quad = \frac{g_m}{{}_o} \qquad g_o \quad |I_C| \quad \text{or} \quad \left|\frac{I_C}{V_A}\right|$$

$$\text{C} \quad = g_m \;{}_b + \text{ B-E depletion capacitance, where } \quad {}_b = \frac{w_B^2}{2D_{\substack{minority\\ .in\ base}}}$$

$$C \quad = \text{ B-C depletion capacitance}$$

MOSFET (in saturation)

$$g_m \quad \sqrt{2K\,|I_D|} = \text{K}|\text{V}_{\text{GS}} - \text{V}_{\text{T}}| = \frac{2I_D}{(\text{V}_{\text{GS}} - \text{V}_{\text{T}})} \qquad g_o \quad |I_D| \quad \text{or} \quad \left|\frac{I_D}{V_A}\right|$$

$$g_{mb} = \quad g_m = \quad \sqrt{2K\,|I_D|} \qquad \text{with} \qquad = \frac{1}{C_{ox}^*}\sqrt{\frac{{}_{Si} q N_A}{\left|q \;{}_p\right| \quad V_{BS}}}$$

$$C_{gs} = \frac{2}{3} W L C_{ox}^* \qquad C_{sb}, C_{gb}, C_{db}: \text{ depletion region capacitances}$$

$$C_{gd} = W\, C_{gd}^* \quad \text{where } C_{gd}^* \text{ is the gate-to-drain fringing and overlap capacitance per unit gate width}$$

Single transistor analog circuit building block stages

Bipolar:-based stages

	Voltage gain, A_v	Current gain, A_i	Input resistance, R_i	Output resistance, R_o
Common emitter	$\frac{g_m}{[g_o+g_l]}$ $(= \ \ g_m r_l')$	$\frac{g_l}{[g_o+g_l]}$	r	$r_o \quad = \frac{1}{g_o}$
Common base	$\frac{g_m}{[g_o+g_l]}$ $(= g_m r_l')$	1	$\frac{r}{[\ \ +1]}$	$[\ \ +1] r_o$
Emitter follower	$\frac{[g_m+g\ \ ]}{[g_m+g\ \ +g_o+g_l]}$ 1	$\frac{g_l}{[g_o+g_l]}$	$r\ \ +[\ \ +1] r_l'$	$\frac{r_t+r}{[\ \ +1]}$
Emitter degeneration (series feedback)	$-\frac{r_l}{R_F}$		r $+[\ \ +1] R_F$	r_o
Shunt feedback	$\frac{[g_m \ \ \ G_F]}{[g_o+G_F]}$ $\quad g_m R_F$	$\frac{g_l}{G_F}$	$\frac{1}{g\ \ +G_F[1 \ \ \ A_v]}$	$r_o \| R_F \quad = \frac{1}{[g_o+G_F]}$

MOSFET-based stages

	Voltage gain, A_v	Current gain, A_i	Input resistance, R_i	Output resistance, R_o
Common source	$g_m r_l'$	•	•	$r_o \quad = \frac{1}{g_o}$
Common gate	$[g_m+g_{mb}] r_l'$	1	$\frac{1}{[g_m+g_{mb}]}$	$r_o \ \ 1+\frac{[g_m+g_{mb}+g_o]}{g_t}$
Source follower	$\frac{g_m}{[g_m+g_o+g_l]}$ $\quad 1$	•	•	$\frac{1}{[g_m+g_o+g_l]} \quad \frac{1}{g_m}$
Source degeneration (series feedback)	$-\frac{r_l}{R_F}$	•	•	r_o
Shunt feedback	$\frac{[g_m \ \ \ G_F]}{[g_o+G_F]}$ $\quad g_m R_F$	$\frac{g_l}{G_F}$	$\frac{R_F}{G_F[1 \ \ \ A_v]}$	$r_o \| R_F \quad = \frac{1}{[g_o+G_F]}$

OCTC/SCTC

OCTC estimation of $_{HI}$: $\quad _{HI} \quad \Big[\underset{i}{} \ \ _i \Big]^{1} \quad = \quad \underset{i}{} R_i C_i$ [1] [1]

with R_i defined as the equivalent resistance in parallel with C_i, with all other parasitic device C's (C 's, C 's, C_{gs}'s, C_{gd}'s, etc.) open circuited.

SCTC estimation of $_{LO}$: $\quad _{LO} \geq \underset{j}{} \ \ _j = \underset{j}{} \big[R_j C_j \big]^{1}$ [1]

with R_j defined as the equivalent resistance in parallel with C_j, with all other biasing and coupling C's (C_I's, C_O's, C_E's, C_S's, etc.) short circuited.

Difference- and Common-mode signals

Given two signals, v_1 and v_2, we can decompose them into two new signals, one (v_C) that is common to both v_1 and v_2, and one (v_D) that makes an equal, but opposite polarity, contribution to v_1 and v_2:

$$v_D \equiv v_1 \quad v_2 \text{ and } v_C \equiv \frac{[v_1 + v_2]}{2} \qquad v_1 = v_C + \frac{v_D}{2} \text{ and } v_2 = v_C \quad \frac{v_D}{2}$$

CMOS performance

Transfer characteristic

$$\text{In general: } V_{LO} = 0, \quad V_{HI} = V_{DD}, \quad I_{ON} = 0, \quad I_{OFF} = 0$$

$$\text{Symmetry: } V_M = \frac{V_{DD}}{2} \text{ and } N_{ML} = N_{MH} \qquad K_n = K_p \text{ and } |V_{Tp}| = V_{Tn}$$

$$\text{Minimum size gate: } L_n = L_p = L_{\min}, \quad W_p = \left({}_n / {}_p \right) W_n, \quad W_n = W_{\min}$$

Switching trimes and Gate delay

$$_{Charge} = {}_{Discharge} \quad \frac{2V_{DD}C_L}{K_n [V_{DD} \quad V_{Tn}]^2}$$

$$C_L = n\left(W_n L_n + W_p L_p\right) C_{ox}^* = 3nW_{\min} L_{\min} C_{ox}^* \qquad \text{assumes } {}_e = 2 \ {}_h$$

$$_{Min.Cycle} = {}_{Charge} + {}_{Discharge} \quad \frac{12nL_{\min}^2 V_{DD}}{{}_e [V_{DD} \quad V_{Tn}]^2}$$

:Power disippation

$$P_{ave@Max.f} = C_L V_{DD}^2 f_{\max} \ \mu \ C_L V_{DD}^2 / {}_{Min.Cycle} = \frac{{}_e W_{\min} C_{ox}^* V_{DD} [V_{DD} \quad V_{Tn}]^2}{L_{\min}}$$

$$PD_{ave@Max.f} = \frac{P_{ave@Max.f}}{\text{Inverter area}} \ \mu \ \frac{P_{ave@Max.f}}{W_{\min} L_{\min}} = \frac{{}_e \ {}_{ox} V_{DD} [V_{DD} \quad V_{Tn}]^2}{t_{ox} \ L_{\min}^2}$$